

	Type	Hits	Search Text	DBs	Time Stamp	Comments	Error	Ratio
1	BRS	1	multilevel near euv	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/22 16:05			0
2	BRS	2	multilevel and euv near diffuser	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/20 19:36			0
3	BRS	4	euv near diffuser	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/20 19:37			0
4	BRS	15	diffract\$6 and optic\$6 with euv and diffuser	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/20 19:40			0
5	BRS	4	diffract\$6 with euv and optic\$6 and reflect\$6 near mode and diffuser	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/20 19:41			0
6	BRS	4	diffract\$6 with euv and reflect\$6 near mode and diffuser	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/20 19:41			0
7	BRS	4	diffract\$6 with euv and reflect\$6 near mode and diffus\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/20 19:42			0
8	BRS	4	diffract\$6 with euv and reflect\$6 near mode	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/20 19:42			0
9	BRS	11	diffract\$6 with euv and reflect\$6 and diffus\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/20 19:44			0
10	BRS	3	diffract\$6 and euv with reflect\$6 with mode and diffus\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/20 19:45			0

	Type	Hits	Search Text	DBs	Time Stamp	Comments	Error	Errors
11	BRS	55	diffract\$6 and euv with reflect\$6 and diffus\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/20 19:45			0
12	BRS	12	diffract\$6 and reflect\$6 and euv with diffus\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/21 09:03			0
13	BRS	25 49	euv	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/22 16:05			0
14	BRS	11 5	euv and (curable or cured or curing or cure)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/22 16:07			0
15	BRS	60	(curable or cured or curing or cure) and reflect\$6 with (film or layer euv and	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/22 16:08			0
16	BRS	10	(curable or cured or curing or cure) with reflect\$6 with (film or layer euv and	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/22 16:09			0
17	BRS	10	(curable or cured or curing or cure) with reflect\$6 with (film or layer) and sub	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/22 16:16			0
18	BRS	1	strate with (low adj k or bcb or sog or hsq) and stack with reflect\$6 with (film or layer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/22 16:18			0

	Type	Hits	Search Text	DBs	Time Stamp	Comments	Error	Errors
19	BRS	1	euv and substrate with (low adj k or bcb or sog or hsq) and (stack or multil\$6 or second) with reflect\$6 with (film or layer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/22 16:20			0
20	BRS	406	euv and (stack or multil\$6 or second) with reflect\$6 with (film or layer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/22 16:20			0
21	BRS	15	euv with diffus\$6 and (stack or multil\$6 or second) with reflect\$6 with (film or layer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/22 16:34			0
22	BRS	52	euv with mirror and diffus\$6 and (stack or multi\$6 or second) with reflect\$6 with (film or layer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/22 16:35			0
23	BRS	37	euv with mirror and diffus\$6 and (stack or multi\$6 or second) with reflect\$6 with (film or layer) and cur	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/22 16:45			0

	Type	Hits	Search Text	DBs	Time Stamp	Comments	Errors
24	BRS	1	euv with mirror and diffus\$6 and (stack or multi\$6 or second) with reflect\$6 with (film or layer) and substrate with	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/22 16:46		0
25	BRS	10	euv with mirror and diffus\$6 and (stack or multi\$6 or second) with reflect\$6 with (film or layer) and substrate with (photoresist or dielectric)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/22 16:47		0
26	BRS	48	euv with mirror and (stack or multi\$6 or second) with reflect\$6 with (film or layer) and substrate with (photoresist or dielectric)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/22 17:14		0
27	BRS	5	euv and mirror and (stack or multi\$6 or second) with reflect\$6 with (film or layer) and substrate near (photoresist or protect\$6 or dielectric)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/22 17:16		0